

REMARKS

Examiner W. Wright is thanked for the thorough examination and search of the subject Patent Application. Claims 16, 17, 27, 29, 30, and 32 have been amended and Claims 28, 31, and 33 have been canceled.

Claims 27, 29, 30, and 32 have been amended and Claims 28, 31, and 33 have been canceled to overcome objection and rejection under 35 U.S.C. 112, second paragraph. The further process steps of Claims 28, 31, and 33 have been incorporated into their respective independent claims. Claim 29 has been amended to depend on amended Claim 27.

All Claims are believed to be in condition for Allowance, and that is so requested.

Reconsideration of the rejection under 35 U.S.C. 103 of Claims 16, 17, and 26-33 as being unpatentable over De Santis is requested in view of Amended Claims 16, 27 and 30 and in accordance with the following remarks.

The scrubbing of De Santis takes place within the aspiration section 11 and the orifice section 12 (col. 5, line 60 – col. 6, line 14) of the scrubber shown in Fig. 1. When the gas enters the separation housing 34, it has already been scrubbed (col. 6, lines 21-24). While it is agreed that the silicon dioxide is separated out of the spent scrubbing liquid in the separation chamber (col. 6, lines 34-42), this is not the same process taught in Applicants' invention. In Applicants' invention, the scrubbing takes place under the water within the water-filled chamber. On page 5 of the Specification, it is taught that the silane gas enters

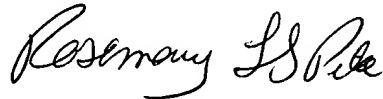
the water-filled chamber under the water (see claims 26, 27, and 30 and Fig. 1, 24). Claims 16, 27, and 30 have been amended to claim flowing N₂ gas to push the waste silane into the water-filled chamber (incorporated from their respective dependent claims). In Claim 16, the gas is bubbled into the water-filled chamber. This implies that the gas enters the chamber under the water. Claims 27 and 30 specifically claim that the waste silane gas enters the water-filled chamber under the water. The reaction of the silane gas with oxygen takes place within the water. The oxygen is dissolved in the water in the chamber. There is no teaching or suggestion in De Santis that the scrubbing take place within the separation chamber 34. Scrubbing takes place within the flow of scrubbing liquid (col. 5, line 60 – col. 6, line 14). Applicants' invention does not require the extra complexity of the scrubbing liquid flow and jet pump of De Santis. Claims 27 and 30 recite the steps "consisting of" those steps listed. Only the steps of: 1) flowing N₂ gas at high pressure to push the waste silane gas into the water-filled chamber, 2) reacting the waste silane with oxygen dissolved in the water-filled chamber, and 3) draining the SiO₂ precipitates out of the water-filled chamber are required in the silane abatement process of Applicants' invention. The extra steps of De Santis involving the scrubbing jet pumps, the orifice section that provides pressure drop (col. 6, lines 2-8), separation housing, and gas outlet ports (col. 6, lines 21-34) are not required in Applicants' invention.

Reconsideration of the rejection under 35 U.S.C. 103 of Claims 16, 17, and 26-33 as being unpatentable over De Santis is requested in view of Amended claims 27 and 30 and in accordance with the remarks above.

Allowance of all Claims is requested.

It is requested that should Examiner Wright not find that the Claims are now Allowable that the Examiner call the undersigned at 765 4530866 to overcome any problems preventing allowance.

Respectfully submitted,

A handwritten signature in cursive script, reading "Rosemary L. S. Pike". The signature is written in black ink and is positioned above the printed name.

Rosemary L. S. Pike. Reg # 39,332